

Cleaning recommendation

Filter elements and inlet filters of the F-MI filter series



General information

(1) These cleaning instructions are to be understood as a recommendation. It is **not** guaranteed that complete cleaning or the new condition of the filter element will be achieved. If the filter performance after cleaning differs noticeably from that of a new filter element, the filter element must be replaced.

- Before cleaning the filter element, remove the O-ring, if present
- Always handle filter elements by the solid parts and not by the filter surface 1
- Depending on the type of contamination, suitable cleaning media must be used (see following flow charts)

- The outlet port 2 of the filter element must be open during the entire cleaning process.
- During the entire cleaning procedure, no unfiltered medium may enter the interior of the filter through the outlet opening 2 of the filter element. If possible, connect a clean piece of hose to the filter element for the cleaning procedure in the ultrasonic bath using a hose nozzle, the upper end of which protrudes from the ultrasonic bath. The hose also makes it easier to rinse the filter element and blow it out with compressed air.
- A 10 µm filter is recommended for filtering the rinsing and solution media. In particular, the mesh size must not be larger than the mesh size of the filter to be cleaned.

- Always store unpacked filter elements upside down (outlet port 2 pointing downwards) to prevent dust particles out of the air from entering the filter interior.
- Storage of filter elements only in clean, lowparticle packaging (e.g. in twist packs)

▲ Attention! In a µDispense or a functional module, the flow through the F-MI0 filter element is in the opposite direction. Therefore, when cleaning, the filter element must be positioned upside down and flushed from the outside to the inside.

Cleaning instructions according to contamination type

On the following pages, three different cleaning sequences are shown schematically. The selection of the suitable sequence is made depending on the contamination with

- A Aqueous media and for fouling
- B Nucleic acids (DNA)
- C Other media / particle loading.



A Cleaning after contamination with aqueous media and for fouling					
1. Alkaline cleaning	2. Rinsing	3. Acid cleaning	4. Rinsing		
55 - 65 °C / 130 - 150 °F ≥ 10 min PH 10 - 12	I Sector	55 - 65 °C / 130 - 150 °F ≥ 10 min pH 3 - 4	T S S S S S S S S S S S S S		
Ultrasonic bath with alkaline cleaning solution (if possible with surfactant)	Alternately rinsing with DI water and blowing out with compressed air until the air comes out bubble- free when blowing out	Ultrasonic bath with acid cleaning solution	Alternately rinsing with DI water and blowing out with compressed air until the air comes out bubble- free when blowing out		
5. Neutral cleaning	6. Rinsing		7. Drying		
Ultrasonic bath with DI water	Alternately rinsing with DI water and blowing out with compressed air until the air comes out bubble- free when blowing out	If the filter element is not reused immediately, carry out the following steps 7 and 8.	Image: State sta		
8. Packaging		1			
Pack the filter element for further storage (see General information)					

Reference for above items: A



Filter element

DI water





Drying cabinet / oven

Acid detergent (pH 3 – 4)

DI water



Alkaline detergent (pH 10 – 12) Compressed air (≤ 4 bar)

Contact HNP Mikrosysteme GmbH Bleicherufer 25 · D-19053 Schwerin

phone fax

+49 385 52190-301 +49 385 52190-333 e-mail info@hnp-mikrosysteme.de https://www.hnp-mikrosysteme.de



B Cleaning after contamination with nucleic acids (DNA)					
1. Acid cleaning	2. Rinsing	3. Alkaline cleaning	4. Rinsing		
55 - 65 °C / 130 - 150 °F ≥ 10 min pH 3 - 4	T S 4 bar/ ≤ 60 psi	55 - 65 °C / 130 - 150 °F ≥ 10 min pH 10 - 12	I S 4 bar/ ≤ 60 psi		
Ultrasonic bath with acid cleaning solution	Alternately rinsing with DI water and blowing out with compressed air until the air comes out bubble- free when blowing out	Ultrasonic bath with alkaline cleaning solution (if possible with surfactant)	Alternately rinsing with DI water and blowing out with compressed air until the air comes out bubble- free when blowing out		
5. Neutral cleaning	6. Rinsing		7. Drying		
55 - 65 °C / 130 - 150 °F ≥ 10 min	Alternation visite Diverter	If the filter element is not reused immediately, carry out the following steps 7 and 8.	Structure desired (support		
Ultrasonic bath with DI water	and blowing out with compressed air until the air comes out bubble- free when blowing out		Attention! Put the filter upside down (see General information). Alternative: Drying for 2 days at 20 – 25 °C room temperature		
8. Packaging					
Pack the filter element for further storage (see General information)					

Reference for above items: B

DI water

Filter element

Ultrasonic bath

Drying cabinet / oven

Acid detergent (pH 3 – 4)

DI water

Alkaline detergent (pH 10 – 12) Compressed air (≤ 4 bar)

Contact HNP Mikrosysteme GmbH Bleicherufer 25 · D-19053 Schwerin

phone fax

+49 385 52190-301 +49 385 52190-333 e-mail info@hnp-mikrosysteme.de https://www.hnp-mikrosysteme.de

C Cleaning after contamination with other media / particle loading					
1a. Cleaning	1b. Cleaning	2. Flushing	3. Rinsing		
individual individual	pr		↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓		
Ultrasonic bath with solvent; adjust duration and temperature to type and degree of contamination	Immersion bath with solvent; adjust duration and temperature to type and degree of contamination	Rinsing from the inside to the outside with solvent for particle removal Attention! Do not perform any additional mechanical cleaning from the outside	Alternately rinsing with DI water and blowing out with compressed air until the air comes out bubble- free when blowing out		
	4. Acid cleaning	5. Rinsing	6. Neutral cleaning		
If the filter element is not reused immediately, carry out the following steps 4 and 10.	Ultrasonic bath with acid cleaning	Alternately rinsing with DI water	Ultrasonic bath with DI water		
	solution	and blowing out with compressed air until the air comes out bubble- free when blowing out			
7. Rinsing	9. Drying	10. Packaging			
I I I I I I I I I I I I I I I I I I I	<pre>≤ 150 °C / ≤ 302 °F ≥ 120 min</pre>				
Alternately rinsing with DI water and blowing out with compressed air until the air comes out bubble- free when blowing out	Dry in drying cabinet / oven Attention! Put the filter upside down (see General information). Alternative: Drying for 2 days at 20 – 25 °C room temperature	Pack the filter element for further storage (see General information)			

Reference for above items: C

Contact HNP Mikrosysteme GmbH Bleicherufer 25 · D-19053 Schwerin

phone fax

+49 385 52190-301 +49 385 52190-333 e-mail info@hnp-mikrosysteme.de https://www.hnp-mikrosysteme.de